Work report 140220: Co-sputtered ZnO-SnO₂

Rob Treharne

March 4, 2014

1 Overview

Deposition and optical characterisation of co-sputtered Zn-Sn-O films on OptiWhite and Si substrates. Samples sent to Robert Palgrave, UCL. Film profiles determined using ellipsometry - interpolated from 81pt measurement grid over 8×8 cm² central area. Identical samples sent to Cranfield University (XRD mapping) and Binghampton, NY (HAXAS, UPS)

2 Film recipe

• Material: ZnO:SnO₂ (co-sputtered)

• Power (W): 250:80

• Pressure (mTorr): 5 (Ar)

• Growth Time: 60 min

• Rotation: OFF

3 Film profiles

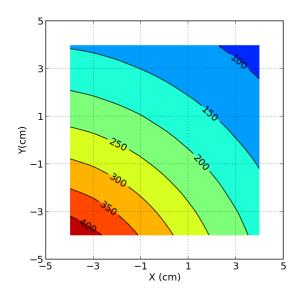


Figure 1: ZnO calibration sample. Contours show film thickness (in nm).

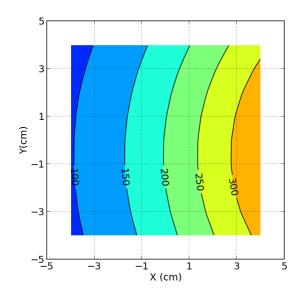
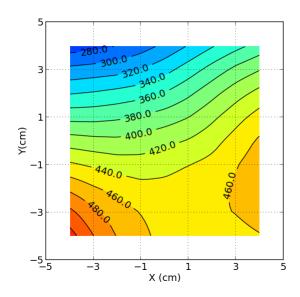


Figure 2: SnO₂ calibration sample. Contours show film thickness (in nm).



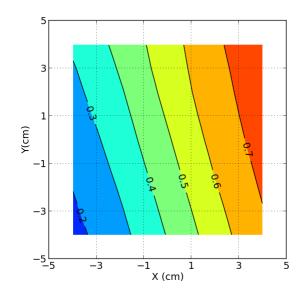


Figure 3: Calculated thickness of co-sputtered $\rm ZnO:SnO_2$ film. Contours show film thickness (in nm).

Figure 4: Profile of ratio $d_{SnO_2}/(d_{ZnO}+d_{SnO_2})$ calculated using figures 1 and 2.



Figure 5: Sample 140220_2. Cut into $4.5 \times 5 \text{ cm}^2$ pieces. Orientation of sample in this photo corresponds directly with profile shown in figure 4. Note: Film side is face-up in this photo.

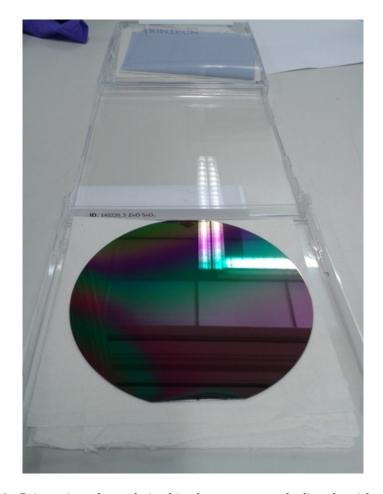


Figure 6: Sample 140220 $_$ 3. Orientation of sample in this photo corresponds directly with the profile showin in figure 4